## IN THE CLAIMS

Claims 1-5 (cancelled).

- 6. (original) An integrated circuit comprising a semiconductor substrate and a nonvolatile memory cell having an active area formed in the semiconductor substrate, the memory cell comprising:
  - a dielectric on the active area; and
- a floating gate on the dielectric, the floating gate having a horizontal top surface projecting laterally beyond the active area.
- 7. (original) The integrated circuit of Claim 6 wherein at a location at which the top surface of the floating gate projects beyond the active area, the floating gate has a sidewall, and at least a top portion of the sidewall extends laterally outward and beyond the active area as the sidewall is traced upward.
- 8. (original) The integrated circuit of Claim 7 further comprising a dielectric region abutting said top portion of the sidewall.
- 9. (original) An integrated circuit comprising a semiconductor substrate and a nonvolatile memory cell having an active area formed in the semiconductor substrate, the memory cell comprising:
  - a dielectric on the active area; and
- a floating gate on the dielectric, wherein the floating gate has a sidewall, and at least a top portion of the sidewall extends laterally outward as the sidewall is traced upward.
- 10. (original) The integrated circuit of Claim 9 further comprising a dielectric region physically contacting, and extending along, said top portion of the sidewall.

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